

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended): A silica glass crucible used for pulling silicon single crystal, comprising:

a silica glass crucible having a wall part, an open diameter, an inner surface, and an outer surface; and

a graphite susceptor adhered to the outer surface of the silica glass crucible;

wherein at least an outer surface of a the wall part of the crucible is covered with fine grooves having a length of from 10  $\mu\text{m}$  to less than 200 $\mu\text{m}$ , a width of from 10  $\mu\text{m}$  to less than 30 $\mu\text{m}$  and a depth of from more than 3 $\mu\text{m}$  to less than 30 $\mu\text{m}$ ; and

wherein a sliding frictional coefficient of the outer surface of the crucible to the graphite susceptor at 1500°C is more than 0.6.

Claim 2 (Original): The silica glass crucible according to Claim 1,  
wherein the fine grooves exist on more than 10 % of the outer surface of the crucible.

Claim 3 (Canceled).

Claim 4 (Original): The silica glass crucible according to Claim 1,  
wherein the outer surface of the crucible is covered with the fine grooves by carrying out a sand-blast treatment and a hydrofluoric acid etching on the outer surface.

Claim 5 (Original): The silica glass crucible according to Claim 1,  
wherein the number of projections having a height of 0.1 mm or more is an average of less than 5 /  $\text{mm}^2$  per unit area on the outer surface of the crucible.

Claim 6 (Currently Amended): A silica glass crucible used for pulling silicon single crystal, comprising:

a silica glass crucible having a wall part, an open diameter, an inner surface, and an outer surface; and

a graphite susceptor adhered to the outer surface of the silica glass crucible;

wherein at least an outer surface of a the wall part of the crucible is covered with fine grooves having a length of from 10  $\mu$ m to less than 200 $\mu$ m, a width of from 10  $\mu$ m to less than 30 $\mu$ m and a depth of from more than 3 $\mu$ m to less than 30 $\mu$ m, and

the fine grooves exist on more than 10 % of the outer surface of the crucible, and

a sliding frictional coefficient of the outer surface of the crucible to the graphite susceptor ~~a carbon member~~ at ~~1500 degree C~~ 1500°C is more than 0.6.

Claim 7 (Currently Amended): A silica glass crucible used for pulling silicon single crystal, comprising:

a silica glass crucible having a wall part, an open diameter, an inner surface, and an outer surface; and

a graphite susceptor adhered to the outer surface of the silica glass crucible;

wherein at least an outer surface of a the wall part of the crucible is covered with fine grooves having a length of from 10  $\mu$ m to less than 200 $\mu$ m, a width of from 10  $\mu$ m to less than 30 $\mu$ m and a depth of from more than 3 $\mu$ m to less than 30 $\mu$ m, and

the fine grooves exist on more than 10 % of the outer surface of the crucible, and

a sliding frictional coefficient of the outer surface of the crucible to the graphite susceptor ~~a carbon member~~ at ~~1500 degree C~~ 1500°C is more than 0.6, and

wherein the outer surface of the crucible has ~~the number of~~ projections having a height of 0.1 mm or more ad the number of projections is an average of less than 5 / mm<sup>2</sup> per unit area on the outer surface of the crucible.

Claim 8 (Withdrawn): A process for forming fine grooves on the surface of a wall part of silica glass crucible used for pulling silicon single crystal, comprising carrying out a sand-blast treatment and a hydrofluoric acid etching on the said surface.

Claim 9 (Withdrawn): A process for forming fine grooves according to Claim 8, wherein fine grooves have a length of less than 200 $\mu$ m, a width of less than 30 $\mu$ m and a depth of from more than 3 $\mu$ m to less than 30 $\mu$ m.

Claim 10 (Withdrawn): A process for forming fine grooves according to Claim 8, wherein the sand-blast treatment is the polishing method by spraying the hard particles having the higher hardness than that of the silica glass, with high pressure gas.

Claim 11 (Withdrawn): A process for forming fine grooves according to Claim 10, wherein the hard particles are the crystalline quartz particles.

Claim 12 (Previously Presented): The silica glass crucible according to Claim 1, wherein the fine grooves have a depth of from more than 3 $\mu$ m to 10 $\mu$ m.

Claim 13 (Previously Presented): The silica glass crucible according to Claim 1, wherein the fine grooves have a length of 10 to 100 $\mu$ m.

Claim 14 (Canceled).

Claim 15 (Previously Presented): The silica glass crucible according to Claim 6, wherein the fine grooves have a depth of from more than  $3\mu\text{m}$  to  $10\mu\text{m}$ .

Claim 16 (Previously Presented): The silica glass crucible according to Claim 6, wherein the fine grooves have a length of 10 to  $100\mu\text{m}$ .

Claim 17 (Canceled).

Claim 18 (Previously Presented): The silica glass crucible according to Claim 7, wherein the fine grooves have a depth of from more than  $3\mu\text{m}$  to  $10\mu\text{m}$ .

Claim 19 (Previously Presented): The silica glass crucible according to Claim 7, wherein the fine grooves have a length of 10 to  $100\mu\text{m}$ .

Claims 20-25 (Canceled).

Claim 26 (New): The silica glass crucible according to Claim 1, wherein the fine grooves are present only on the outer surface of the crucible.

Claim 27 (New): The silica glass crucible according to Claim 6, wherein the fine grooves are present only on the outer surface of the crucible.

Claim 28 (New): The silica glass crucible according to Claim 7, wherein the fine grooves are present only on the outer surface of the crucible.